

Title (en)
ELECTROCHEMICAL DEVICE

Title (de)
ELEKTROCHEMISCHE VORRICHTUNG

Title (fr)
DISPOSITIF ELECTROCHIMIQUE

Publication
EP 1109945 A1 20010627 (FR)

Application
EP 00931328 A 20000519

Priority
• FR 0001388 W 20000519
• FR 9906408 A 19990520

Abstract (en)
[origin: FR2793888A1] A cathodic sputtering target, comprising nickel alloyed with one or more elements for reducing or eliminating ferromagnetism, is new. Independent claims are also included for the following: (i) production of a nickel alloy oxide thin film by magnetic field-assisted cathodic sputtering of the above target in an oxidizing atmosphere; and (ii) an electrochromic device having an active layer produced by the above process and/or from the above target.

IPC 1-7
C23C 14/34; **G02F 1/15**; **C23C 14/08**

IPC 8 full level
C22C 19/03 (2006.01); **C23C 14/08** (2006.01); **C23C 14/34** (2006.01); **G02F 1/1524** (2019.01)

CPC (source: EP KR US)
C22C 19/03 (2013.01 - KR); **C23C 14/085** (2013.01 - EP US); **C23C 14/3414** (2013.01 - EP); **G02F 1/1524** (2018.12 - EP US)

Citation (search report)
See references of WO 0071777A1

Designated contracting state (EPC)
AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

DOCDB simple family (publication)
FR 2793888 A1 20001124; **FR 2793888 B1 20020628**; EP 1109945 A1 20010627; JP 2003500534 A 20030107; JP 5005854 B2 20120822; KR 100686611 B1 20070223; KR 20010070985 A 20010728; WO 0071777 A1 20001130

DOCDB simple family (application)
FR 9906408 A 19990520; EP 00931328 A 20000519; FR 0001388 W 20000519; JP 2000620150 A 20000519; KR 20017000771 A 20010118